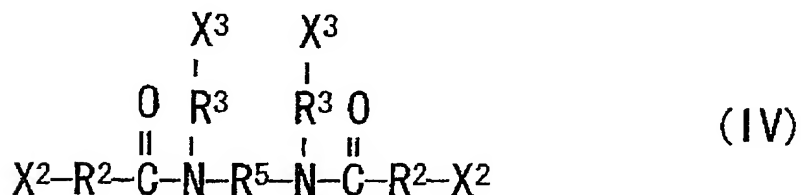
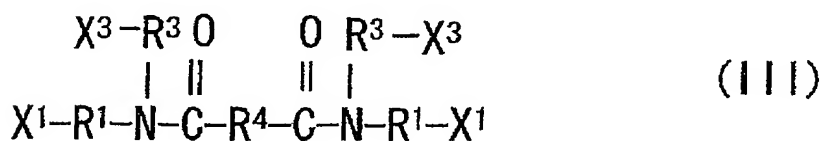
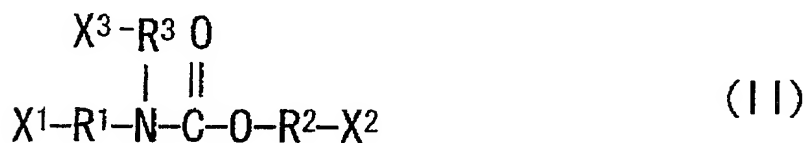
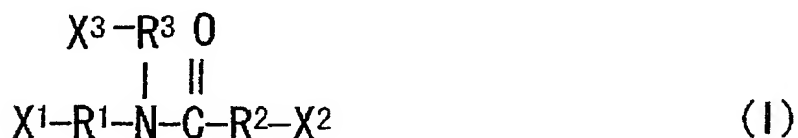


CLAIMS

1. A composition for removing a photoresist comprising at least one compound (A) selected from a group consisting of a compound represented by the following general formula (I), a compound represented by the following general formula (II), a compound represented by the following general formula (III), and a compound represented by the following general formula (IV):



wherein formulas (I) to (IV), R¹ and R³ each independently represent a direct bond, or a linear or branched divalent

hydrocarbon group having 1 to 5 carbon atoms, R^2 represents a linear or branched divalent hydrocarbon group having 1 to 5 carbon atoms, X^1 , X^2 , and X^3 each independently represent a hydrogen atom, an OH group, or an alkyl group having 1 to 5 carbon atoms, and at least one of X^1 , X^2 , and X^3 in each of the formulas (I) to (IV) is an OH group; wherein formulas (III) and (IV), the plurality of R^1 s, R^2 s, and R^3 s, and the plurality of X^1 s, X^2 s, and X^3 s are the same or different; wherein formula (III), R^4 represents a direct bond, or a linear or branched divalent hydrocarbon group having 1 to 5 carbon atoms; and wherein formula (IV), R^5 represents a divalent organic group.

2. The composition according to claim 1, wherein the compound (A) is at least one compound selected from a group consisting of reaction products of ethylene carbonate and primary or secondary organic amines, reaction products of propylene carbonate and primary or secondary organic amines, reaction products of γ -butyrolactone and primary or secondary organic amines, reaction products of 1,3-dihydroxy-2-propanone and primary or secondary organic amines, and dehydration condensation reaction products of mono- or dicarboxylic acids and primary or secondary organic amines.

3. The composition according to claim 2, wherein the compound (A) is at least one compound selected from a group

consisting of bis(2-hydroxyethyl) carbamate,
bis(2-hydroxypropyl) carbamate,
N-(2-hydroxyethyl)-C-(3-hydroxypropyl) amide,
N,N'-bis(2-hydroxyethyl) oxamide,
N,N'-bis(2-hydroxyethyl) malonamide,
(2-hydroxyethyl) acetamide,
N-(2-hydroxyethyl)-N-methyl-C-(3-hydroxypropyl) amide,
N-(2-hydroxyethyl)-N-ethyl-C-(3-hydroxypropyl) amide, and
N,N-bis(2-hydroxyethyl)-C-(3-hydroxypropyl) amide.

4. The composition according to claim 1, wherein at least X^1 and X^2 of the compound (A) are OH groups.

5. The composition according to any one of claims 1 to 4, further comprising an organic amine (B).

6. The composition according to any one of claims 1 to 5, further comprising a water-soluble organic solvent (C).

7. The composition according to any one of claims 1 to 6, further comprising water (D).

8. The composition according to any one of claims 1 to 7, wherein the amount of the compound (A) is from 5 to 100 wt%.

9. A method for removing a photoresist comprising the steps of:

(1) preparing the composition according to any one of claims 1 to 8; and

(2) immersing an object having a photoresist to be removed in the composition.

10. The method according to claim 9, further comprising the step of rinsing the object with water after the step (2).

11. The method according to claim 9 or 10, wherein the photoresist is a positive-type photoresist.